

L Number	Hits	Search Text	DB	Time stamp
1	2034	(359/290,291,294,298,223).CCLS.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/22 15:27
2	8345	micromirror\$1 or micro-mirror\$1 or (micro adj2 mirror\$1)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/22 15:28
3	1843007	substrate\$1	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/22 15:28
4	4925	((first or primary or top) adj2 silicon adj2 layer\$1) and ((second\$3 or bottom) adj2 silicon adj2 layer\$1)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/22 15:29
5	40008	(mirror\$1 or reflect\$3) adj2 (plate\$1 or template\$1 or board\$1)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/22 15:29
6	4809	hydrogen adj2 treatment	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/22 15:29
7	15874	gas near4 sputter\$3	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/22 15:30
8	3888	(micromirror\$1 or micro-mirror\$1 or (micro adj2 mirror\$1)) and substrate\$1	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/22 15:30
9	36	((first or primary or top) adj2 silicon adj2 layer\$1) and ((second\$3 or bottom) adj2 silicon adj2 layer\$1)) and ((micromirror\$1 or micro-mirror\$1 or (micro adj2 mirror\$1)) and substrate\$1)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/22 15:30
10	7	((mirror\$1 or reflect\$3) adj2 (plate\$1 or template\$1 or board\$1)) and (((first or primary or top) adj2 silicon adj2 layer\$1) and ((second\$3 or bottom) adj2 silicon adj2 layer\$1)) and ((micromirror\$1 or micro-mirror\$1 or (micro adj2 mirror\$1)) and substrate\$1))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/22 15:30
11	0	(hydrogen adj2 treatment) and (((mirror\$1 or reflect\$3) adj2 (plate\$1 or template\$1 or board\$1)) and (((first or primary or top) adj2 silicon adj2 layer\$1) and ((second\$3 or bottom) adj2 silicon adj2 layer\$1)) and ((micromirror\$1 or micro-mirror\$1 or (micro adj2 mirror\$1)) and substrate\$1)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/22 15:30
12	100	(hydrogen adj2 treatment) and (gas near4 sputter\$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/22 15:30
13	0	(micromirror\$1 or micro-mirror\$1 or (micro adj2 mirror\$1)) and ((hydrogen adj2 treatment) and (gas near4 sputter\$3))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/22 15:30
14	4	((359/290,291,294,298,223).CCLS.) and (((mirror\$1 or reflect\$3) adj2 (plate\$1 or template\$1 or board\$1)) and (((first or primary or top) adj2 silicon adj2 layer\$1) and ((second\$3 or bottom) adj2 silicon adj2 layer\$1)) and ((micromirror\$1 or micro-mirror\$1 or (micro adj2 mirror\$1)) and substrate\$1)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/22 15:31

15	0	((359/290,291,294,298,223).CCLS.) and ((hydrogen adj2 treatment) and (gas near4 sputter\$3))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/22 15:31
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